

IN THE CONFEED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Leonard Forbes et al.

Examiner:

Donghee Kang

Serial No.:

08/903,486

Group Art Unit:

2811

Filed:

July 29, 1997

Docket:

303.326US1

Title:

SILICON CARBIDE GATE TRANSISTOR

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENTE VED

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 NOV 0 6 2003

Technology Center 2100

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicants respectfully request that this Supplemental Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicants request that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicants with the next official communication.

Pursuant to 37 C.F.R. §1.97(c)(2), Applicants have included the fee of \$180.00 as set forth in 37 C.F.R. §1.17(p). Please charge any additional fees or credit any overpayment to Deposit Account No. 19-0743.

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The Examiner is invited to contact the Applicants' Representative at the below-listed IVED telephone number if there are any questions regarding this communication.

NOV 0 6 2003

Respectfully submitted,

Technology Center 2100

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By their Representatives,

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Date 31 October 2003

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CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this 3152 day of October, 2003.

Signature

Substitute for form 1449A/PTO INFORMATION DISCLOSURE 08/903486 **Application Number** STATEMENT BY APPLICANT July 29, 1997 **Filing Date** (Use as many sheets as necessary) Forbes, Leonard First Named Inventor ed e d hor 2811 group Art Unit Kang, DongheeNOV 0 6 2003 **性**xaminer Name Attorney Docket No: 303.326US1 Technology Center 2100 Sheet 1 of 3

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Sheet 2 of 3

Application Number	08/903486 DECEN/FD
Filing Date	08/903486 July 29, 1997 RECEIVED
First Named Inventor	Forbes, Leonard NOV 0 6 2003
Group Art Unit	2811
Examiner Name	Kang, Dongilechnology Center 210

Attorney	Docket	No:	303	.326	US′	١
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Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE STATEMENT BY APPLICANT **Application Number** 08/903486 July 29, 1997 (Use as many sheets as necessary) **Filing Date** Forbes, Leonard First Named Inventor NOV 0 3 2003 Technology Center 2100 **Group Art Unit** 2811 **Examiner Name** Kang, Donghee Attorney Docket No: 303.326US1 Sheet 3 of 3

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